



NOTES

1. MATERIAL: UVFS
2. CLEAR APERTURE: >90%CA
3. SURFACE QUALITY(S1,S2): 60/40(S/D)
4. WAVEFRONT ERROR(RMS):  $\lambda/4@633$  nm(SUBSTRATE)
5. PARALLELISM(S1,S2): <3 arcmin
6. ARROW POINTS TO THE FILTERING COATING
7. COATING:  
 FILTERING(S1):  $T_{avg}>90\%$ ,  $T_{abs}>85\%@1500-1750$  nm,  $45^\circ$  AOI  
 $R_{avg}>95\%$ ,  $R_{abs}>90\%@1850-2100$  nm,  $45^\circ$  AOI  
 AR COATING(S2):  $R_{abs}<2\%@1500-1750$  nm,  $45^\circ$  AOI

DRAWING PROJECTION			<b>LBTEK</b>			
	NAME	DATE				
DRAWN	LZHOU	JUL./30th/24	SHORTWAVE DICHOIC MIRROR $\phi 12.7$ mm $\times$ 3.2 mm, 1800 nm			
APPROVAL	WCHENG	JUL./30th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	0.9 g	2:1	A